

Title (en)

DEVICE AND METHOD FOR HANDLING PROCESS GASES IN A PLASMA STIMULATED BY HIGH FREQUENCY ELECTROMAGNETIC WAVES

Title (de)

VORRICHTUNG UND VERFAHREN ZUR BEHANDLUNG VON PROZESSGASEN IN EINEM PLASMA ANGEREGT DURCH ELEKTROMAGNETISCHE WELLEN HOHER FREQUENZ

Title (fr)

DISPOSITIF ET PROCÉDÉ POUR TRAITER DES GAZ DE TRAITEMENT DANS UN PLASMA EXCITÉ PAR DES ONDES ÉLECTROMAGNÉTIQUES À HAUTE FRÉQUENCE

Publication

**EP 3011807 A1 20160427 (DE)**

Application

**EP 14744363 A 20140729**

Priority

- DE 102013215252 A 20130802
- EP 2014066277 W 20140729

Abstract (en)

[origin: WO2015014839A1] The invention relates to a device for handling process gases in a plasma stimulated by electromagnetic waves, comprising a plasma chamber, which is lined by a dielectric, a generator for generating the electromagnetic waves and a waveguide assembly for feeding the electromagnetic waves into the plasma chamber, wherein the waveguide assembly has at least two feed points, each having an electric field waveguide branch, for feeding the electromagnetic waves as continuous waves into the dielectric.

IPC 8 full level

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CPC (source: EP)

**H05H 1/46** (2013.01); **H05H 1/461** (2021.05); **H05H 1/4622** (2021.05)

Citation (search report)

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Cited by

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